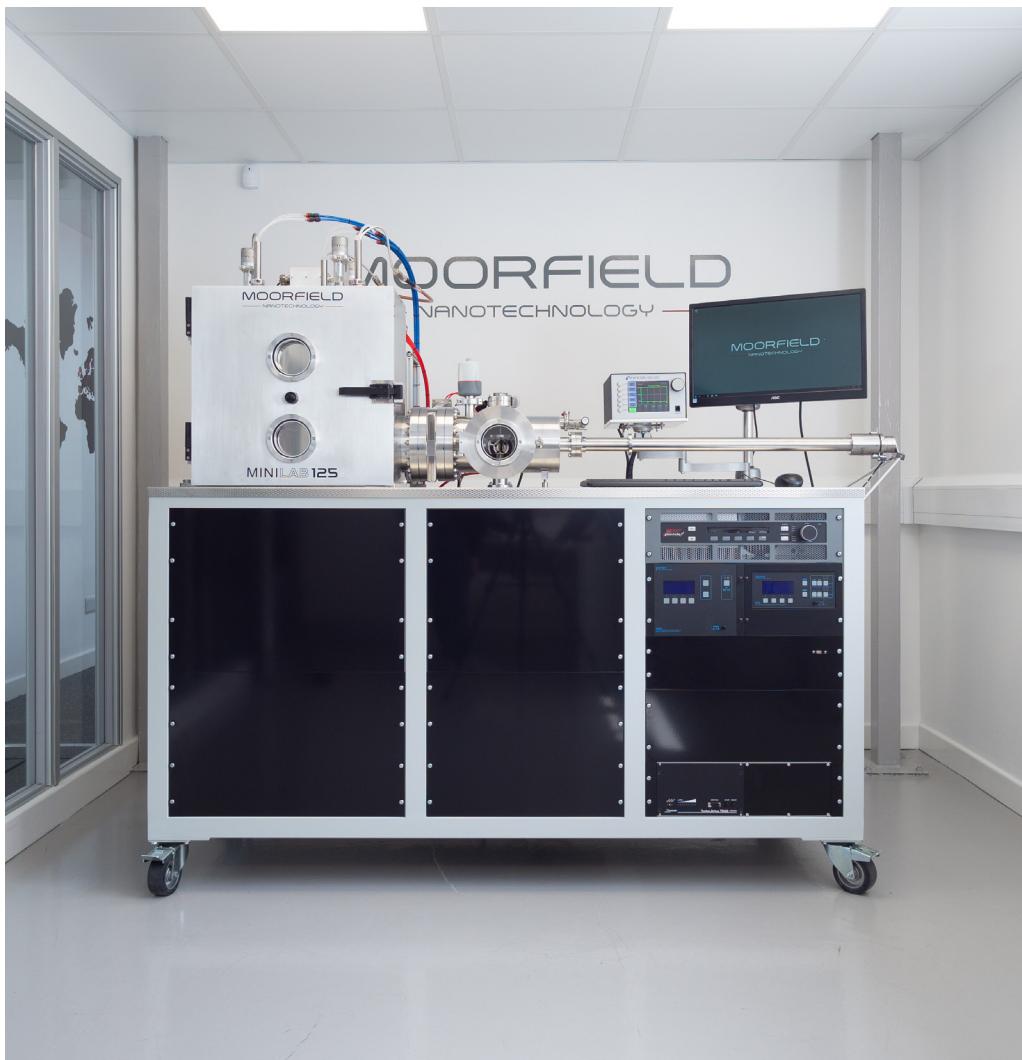


# Minilab 125

Modular system for high-quality physical vapour deposition



## Key features:

- Front-loading box-type vacuum chamber
- Modular design
- Front-loading box-type process chamber
- Turbomolecular/cryogenic pumping systems
- Base pressures  $< 5 \times 10^{-7}$  mbar
- Thermal evaporation
- Low-temperature evaporation (LTE)
- Electron-beam evaporation
- Magnetron sputtering
- Metals, dielectrics and organics deposition
- Up to 11" diameter substrates
- Touchscreen HMI/integrated PC for control
- Easy servicing
- Cleanroom compatible
- Load-locks available
- Proven performance

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## Overview:

MiniLab systems from Moorfield provide superior coating performance, with the flexibility and modularity of design to address a huge range of customer requirements.

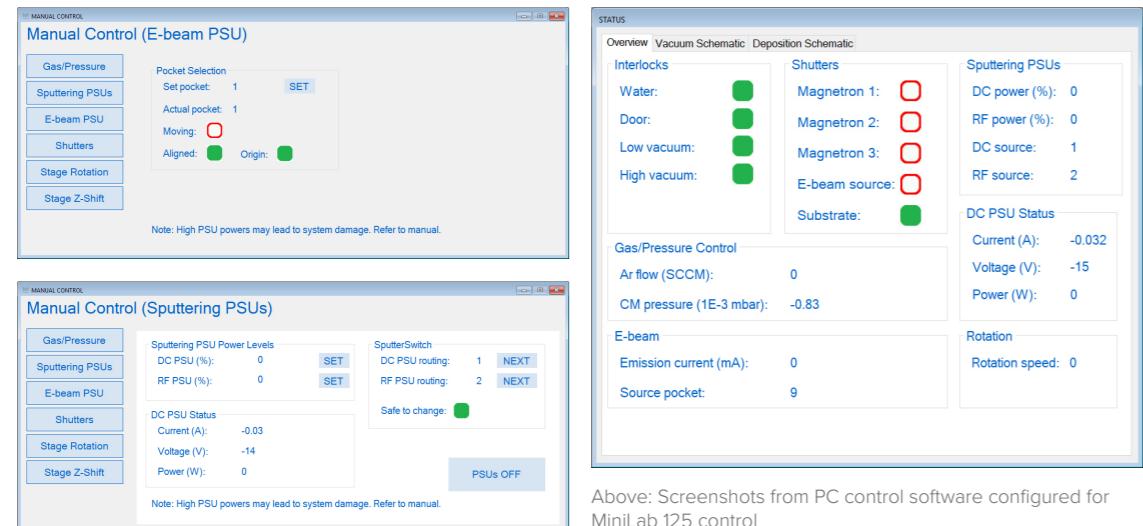
The MiniLab range consists of several platforms. Each platform is generally associated with a specific process chamber size. While all chambers are built to the same standards and allow for high-vacuum operation, larger chambers allow for more techniques and flexibility than their smaller counterparts. In addition to thin-film deposition, MiniLab systems can also be fitted with complementary techniques such as ion beam sources, etching components and annealing stages (platform-dependent).

## MiniLab 125 platform:

MiniLab 125 systems are floor-standing vacuum evaporators for metal, dielectric and/or organics thin-film deposition. All systems contain a box-type stainless-steel chamber with front door for loading/unloading. A turbomolecular pumping system is standard, for high-vacuum base pressures of better than  $5 \times 10^{-7}$  mbar. Exact configuration is extremely flexible and dependent on customer budgets and applications

## Control system:

The unit is fitted with high-stability, industrial-grade PLC electronics. User operation is via a 7" touchscreen HMI or integrated PC. Powerful but easy-to-use software allows for system setup and operation via a menu-driven interface (note that manual control via electronics rack front panels is also possible, depending on exact system configuration). Data-logging and advanced diagnostics are standard features



Above: Screenshots from PC control software configured for MiniLab 125 control

## MiniLab 125 technical specifications:

### Chamber

500 mm x 500 mm footprint, with optional depth (500 or 650 mm) subject to techniques. Box chamber with D-shaped back. Hinged front door for easy access. Chamber baseplate, top and sides fitted with ports for in-chamber hardware. Shuttered viewport(s) for process observation. Viton o-ring seals.

### Safety interlocks

Water and vacuum levels.

### Pumping group

Water-cooled Edwards or Leybold turbomolecular pumps, up to 1500 L/s. Cryogenic pumps also available. Edwards rotary or dry scroll-type backing pumps up to 35 m<sup>3</sup>/hour.

### Pressure measurement

Wide-range gauge (Edwards or Inficon) and optional capacitance manometers for high-resolution measurement.

### Substrate stages

Stainless steel, aluminium or copper with threaded holes for substrate attachment. Up to 11" diameter substrates. Optional rotation, heating, cooling, bias and Z-shift modules.

### Deposition sources

Various types depending on requirements (see above). Separate brochures available for all Moorfield source types.

### Power supplies

Various types depending on integrated techniques. All power supplies fully integrated within system electronics rack.

### System controller

Industrial-grade, high-stability PLC electronics core. Designed for safe operation and reliable vacuum integrity.

### Process monitoring and control

Various components including the Inficon SQM-160 (2-channel monitor) and Inficon SQC-310 (process controller).

### Weight

Approximately 100–200 kg; dependent on configuration.

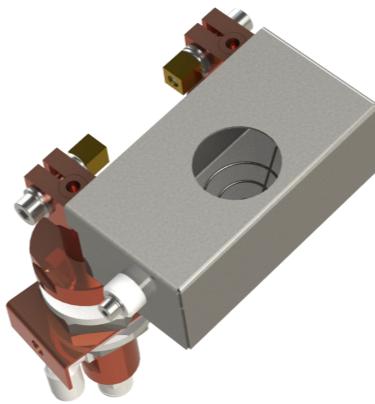
### Size

1700 mm (height) x 590 mm (depth) x 1180 mm (width); dependent on configuration.

## Configuration and options:

The MiniLab 125 base configuration includes a turbomolecular pump positioned on a port at the rear of the process chamber. The chamber sits on a double-rack frame that contains system control electronics and power supplies. MiniLab 125 systems are available with load-locks — please call for details.

The system can be equipped with a wide variety of deposition techniques. These include thermal and low-temperature evaporation sources (for metals and organics), magnetron sputtering cathodes (for metals and inorganics), and electron-beam sources (for most material classes except organics).



Moorfield TE1 source for standard thermal evaporation



Moorfield LTE-1CC source for low-temperature evaporation



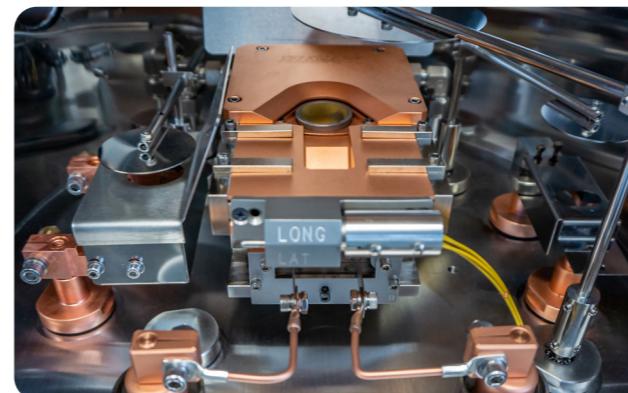
Moorfield Flexi-Head MAGNETRON source for magnetron sputtering

### Thermal evaporation

Up to 4 thermal evaporation sources. Moorfield TE1, TE2, TE3 or TE4 configurations available. Water-cooled power feedthroughs and boxed shielding for excellent vacuum maintenance and low contamination. Power supplies available for automatic, manual, sequential- and co-deposition.

### Low-temperature evaporation

Up to 4 organics sources. Moorfield LTE-1CC, LTE-2CC and LTE-5CC models available. Alumina or quartz crucibles. Power supplies equipped for temperature and power control, in automatic and manual modes.

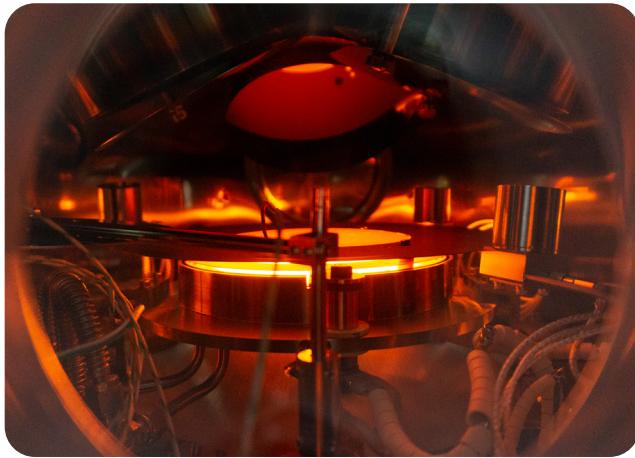


Telemark multi-pocket water-cooled electron-beam source



Multi-technique systems

Various combinations of all of the above can be included in MiniLab 125 systems. For all techniques, deposition rate monitoring (via quartz crystal sensor heads) together with thin-film monitors and controllers are available.



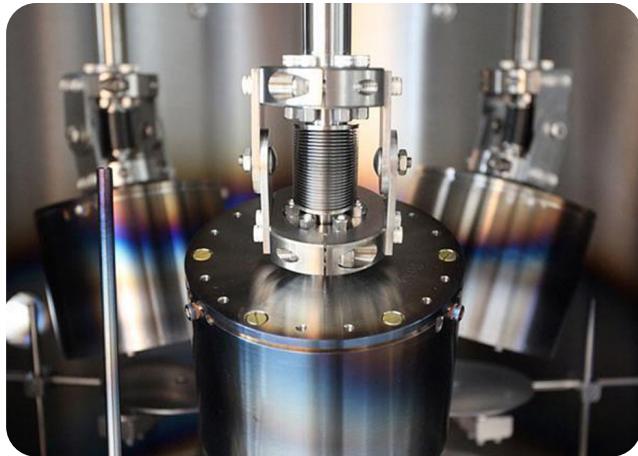
Heater stage seen through the MiniLab 125's chamber viewport



Minilab 125 chamber roof, with removable top-plate allowing for future re-configuration



Inserting substrates into a MiniLab 125 load-lock



Close-up of Moorfield magnetron sources in Minilab 125 system, for sputter-down operation and with flexible head angle and vertical position

## System requirements: (typical configuration)

- Process gases: 25 psi supplies, 99.99% purity or better
- Service gas: Dry compressed air, nitrogen or argon, 60–80 psi supply
- Vent gas: N<sub>2</sub>, 5 psi
- Power: Single-phase 230 V, 50 Hz, 13 A
- Chilled water: 18–20 °C, 3 L/min, pressure < 4 bar
- Exhaust extraction

## Applications:

- Fundamental research
- Education
- Product R&D
- Pilot-scale production

All images/descriptions in this brochure are indicative only; final appearance and design subject to your exact configuration.

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